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ocket No.: Z&P-INFP10443

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By

Date: August 6, 2004

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent No.	:	6,746,827 B2					
Issue Date	:	June 8, 2004					
Patentees	:	Ernst-Christian Richter et al.					
Title	:	Process for Structuring a Photoresist Layer					

Customer No.: 24131

Hon. Commissioner for Patents Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. 1.501

Sir:

In accordance with 37 C.F.R. 1.501, copies of the following patents are cited herewith.

1) U.S. Patent No. 5,206,117 (Labadie et al.), dated April 27, 1993.

The polymer system described therein is a so-called polyamic alkyl ester, which under the influence of a base undergoes a crosslinking reaction via imidazation (see column 4, lines 10 to 26). The carbonic acid ester group COOR' of the general repeat unit of this polymer is supposed to be selected in such a way that it does not interfere with the imidazation or the properties of the final polyimide. Therefore, these ester groups will be relatively stable and cannot be easily cleaved off under the influence of an acid in a photoresist layer.

Most importantly, the polymeric system used therein achieves the modification of the solubility of the final polymer via a crosslinking reaction. Such crosslinking is said to lead to the formation of a three-dimensional network polymer, thereby leading to "rough", i.e.

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imprecisely defined-frayed, for example - profile sidewalls.

A further difference between the present invention and U.S. Patent No. 5,206,117 is that the film-forming polymer is rendered soluble in alkaline solutions in step c) and d) in claim 1 in the above-identified invention, which development is carried out in an alkaline solution.

2) German Published, Non-Prosecuted Patent Application No. DE 100 54 121 A1 (Sebald et al.), dated May 16, 2002, corresponding to U.S. Patent No. 6,746,821 B2.

This reference solely pertains to features cited in the dependent claims of the above-identified patent.

For the above-outlined reasons, it is believed that the enclosed prior art is less pertinent than the prior art previously submitted or cited by the Examiner. It is respectfully requested that the references merely be placed in the PTO file.

Respectfully submitted Greenberg (29,308) Laurenc

Date: August 6, 2004

Lerner And Greenberg, P.A. Post Office Box 2480 Hollywood, FL 33022-2480 Tel: (954) 925-1100 Fax: (954) 925-1101 /bb LAURENCE A. GREENBERG REG. NO. 29,308

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U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))				Attorney Docket No.:Patent No.Z&P-INFP104436,746,827 B2PatenteeErnst-Christian Richter et al.				
				Issue Date June 8, 2004	Group Art Unit 1756			
	-	U.S. I	PATENT	DOCUMENTS				
EXAMINER INITIALS		ΡΑΤΕΝΤ ΝΟ	DATE	PATENTEE	CLASS	SUB CLASS	FIL	
	A	5,206,117	04/93	Labadie et al.				
	В	6,746,821 B2	06/04	Richter et al.	1		1	
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